

Refine Search

Search Results -

Terms	Documents
L52 and ("dose size" or "dose tolerance" or "dose capacity")	1

Database:	US Pre-Grant Publication Full-Text Database US Patents Full-Text Database US OCR Full-Text Database EPO Abstracts Database JPO Abstracts Database Derwent World Patents Index IBM Technical Disclosure Bulletins
------------------	--

Search:	<input style="width: 100%; height: 25px; border: 1px solid black; padding: 2px; font-size: 0.8em;" type="text" value="L53"/>	<input style="width: 100%; height: 25px; border: 1px solid black; padding: 2px; font-size: 0.8em; background-color: #e0e0e0;" type="button" value="Refine Search"/>
		<input style="width: 25px; height: 25px; border: 1px solid black; padding: 2px; font-size: 0.8em; background-color: #e0e0e0;" type="button" value=""/>
<input style="width: 150px; height: 25px; border: 1px solid black; padding: 2px; font-size: 0.8em; background-color: #e0e0e0;" type="button" value="Recall Text"/> <input style="width: 150px; height: 25px; border: 1px solid black; padding: 2px; font-size: 0.8em; background-color: #e0e0e0;" type="button" value="Clear"/> <input style="width: 150px; height: 25px; border: 1px solid black; padding: 2px; font-size: 0.8em; background-color: #e0e0e0;" type="button" value="Interrupt"/>		

Search History

DATE: Wednesday, May 04, 2005 [Printable Copy](#) [Create Case](#)

<u>Set</u>	<u>Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
	side by side			result set
	<i>DB=USPT; PLUR=YES; OP=OR</i>			
<u>L53</u>		l52 and ("dose size" or "dose tolerance" or "dose capacity")	1	<u>L53</u>
<u>L52</u>		L51 and (resist near10 ("multi-layer" or "multi-level"))	241	<u>L52</u>
<u>L51</u>		lithography and resist	14166	<u>L51</u>
<u>L50</u>		"first photoresist" and "second phoresist"	0	<u>L50</u>
<u>L49</u>		48	1194280	<u>L49</u>
<u>L48</u>		"first photoresist" and "second phoresist"p	0	<u>L48</u>
<u>L47</u>		L46 and dose	7	<u>L47</u>
<u>L46</u>		4567132	20	<u>L46</u>
<u>L45</u>		L44	0	<u>L45</u>
		<i>DB=USOC; PLUR=YES; OP=OR</i>		
<u>L44</u>		4,567,132	0	<u>L44</u>
		<i>DB=USPT; PLUR=YES; OP=OR</i>		
<u>L43</u>		4560458	12	<u>L43</u>

<u>L42</u>	6342449	3	<u>L42</u>
<u>L41</u>	L40 near10 opening	1	<u>L41</u>
<u>L40</u>	"50:1" near4 "aspect ratio"	147	<u>L40</u>
<u>L39</u>	L38	12	<u>L39</u>
<u>L38</u>	4560458	12	<u>L38</u>
<u>L37</u>	6693038	1	<u>L37</u>
<u>L36</u>	6342449	3	<u>L36</u>
<u>L35</u>	634449	10	<u>L35</u>
<u>L34</u>	L32	0	<u>L34</u>
<u>L33</u>	L32	0	<u>L33</u>
<i>DB=USOC; PLUR=YES; OP=OR</i>			
<u>L32</u>	6342449	0	<u>L32</u>
<u>L31</u>	L30	0	<u>L31</u>
<i>DB=TDBD; PLUR=YES; OP=OR</i>			
<u>L30</u>	L29	0	<u>L30</u>
<i>DB=DWPI; PLUR=YES; OP=OR</i>			
<u>L29</u>	L28	0	<u>L29</u>
<i>DB=EPAB; PLUR=YES; OP=OR</i>			
<u>L28</u>	L27	0	<u>L28</u>
<i>DB=JPAB; PLUR=YES; OP=OR</i>			
<u>L27</u>	(contact or via) and L24	0	<u>L27</u>
<i>DB=PGPB; PLUR=YES; OP=OR</i>			
<u>L26</u>	L25	0	<u>L26</u>
<i>DB=USPT; PLUR=YES; OP=OR</i>			
<u>L25</u>	(contact or via) and L24	22	<u>L25</u>
<u>L24</u>	L23 and (form\$5 near5 conduct\$4 near6 etched)	25	<u>L24</u>
<u>L23</u>	(doped or diffused) same (lateral\$3 near5 etch\$5)	405	<u>L23</u>
<u>L22</u>	"etch ratio" and plasma and l7	6	<u>L22</u>
<u>L21</u>	L9 and "etch raio"	0	<u>L21</u>
<u>L20</u>	L17 same torr	24	<u>L20</u>
<u>L19</u>	L17 torr	59732	<u>L19</u>
<u>L18</u>	L17 same "mT"	0	<u>L18</u>
<u>L17</u>	L15 near10 fluorine	139	<u>L17</u>
<u>L16</u>	L15 near10 fluorine9	0	<u>L16</u>
<u>L15</u>	(plasma)near8 pressure	17721	<u>L15</u>
<u>L14</u>	L13 same fluorine	4	<u>L14</u>
<u>L13</u>	(forming near5 plasma)near8 pressure	554	<u>L13</u>
<u>L12</u>	L11 same (opening or hole or via)	12	<u>L12</u>
<u>L11</u>	(fluorine near5 gas) near7 ((etch\$4) near 10("titanium" or "titanium-nitride" or titanium compound" or titanium alloy"))	53	<u>L11</u>
<u>L10</u>	(fluorine near5 gas) near7 ((dielectric or insulat\$5) near5 (etch\$5)) near10 temperature	4	<u>L10</u>

<u>L9</u>	(fluorine near5 gas) near7 (etch\$5) near10 temperature	67	<u>L9</u>
<u>L8</u>	L7	507	<u>L8</u>
<u>L7</u>	(fluorine near5 gas) same (etch\$5) same temperature	507	<u>L7</u>
<u>L6</u>	6451705 and (etch\$5 near4 temperature)	2	<u>L6</u>
<u>L5</u>	L1 and (etch\$5 near14 temperature)	0	<u>L5</u>
<u>L4</u>	L1 and (etch\$5 near4 temperature)	0	<u>L4</u>
<u>L3</u>	L1 and temperature	4	<u>L3</u>
<u>L2</u>	L1 and temperature	1305302	<u>L2</u>
<u>L1</u>	6720256	4	<u>L1</u>

END OF SEARCH HISTORY

Refine Search

Search Results -

Terms	Documents
L74	0

Database:

US Pre-Grant Publication Full-Text Database
 US Patents Full-Text Database
 US OCR Full-Text Database
 EPO Abstracts Database
 JPO Abstracts Database
 Derwent World Patents Index
 IBM Technical Disclosure Bulletins

Search:

Search History

DATE: Wednesday, May 04, 2005 [Printable Copy](#) [Create Case](#)

Set	Hit	Set
Name	Count	Name
side by side		result set
DB=USPT; PLUR=YES; OP=OR		
<u>L75</u> L74	0	<u>L75</u>
<u>L74</u> (photolithography same ("GKRS 6202") same ("ARCH 8250"))	0	<u>L74</u>
DB=PGPB; PLUR=YES; OP=OR		
<u>L73</u> L72	0	<u>L73</u>
DB=TDBD; PLUR=YES; OP=OR		
<u>L72</u> L71	0	<u>L72</u>
DB=DWPI; PLUR=YES; OP=OR		
<u>L71</u> L70	0	<u>L71</u>
DB=JPAB; PLUR=YES; OP=OR		
<u>L70</u> L69	0	<u>L70</u>
DB=EPAB; PLUR=YES; OP=OR		
<u>L69</u> L68	0	<u>L69</u>
DB=USOC; PLUR=YES; OP=OR		

<u>L68</u>	<u>L67</u>	0	<u>L68</u>
<i>DB=USPT; PLUR=YES; OP=OR</i>			
<u>L67</u>	(photolithography same (GKRS 6202) same (ARCH 8250))	0	<u>L67</u>
<u>L66</u>	(lithography same (GKRS 6202) same (ARCH 8250))	0	<u>L66</u>
<u>L65</u>	(photoresist\$) same (acetal near10 polymer\$)	99	<u>L65</u>
<u>L64</u>	L63 and (acetal near10 polymer\$)	0	<u>L64</u>
<u>L63</u>	("ethyl lactate" near5 solvent) same positive same negative same photoresist\$	1	<u>L63</u>
<u>L62</u>	(("common" or "generic") near5 ("solvent" or "solvents")) near10 ("photoresists")	44	<u>L62</u>
<u>L61</u>	(("common" or "generic") near5 ("solvent" or "solvents")) near 10 ("photoresists")	66412	<u>L61</u>
<u>L60</u>	L59 near10 ("common" or "generic")	980	<u>L60</u>
<u>L59</u>	solvent\$ near 10 ("photoresists")	70524	<u>L59</u>
<u>L58</u>	photoresist near10 ("common solvent" or "generic solvent")	12	<u>L58</u>
<u>L57</u>	photoresist same ("common solvent" or "generic solvent")	52	<u>L57</u>
<u>L56</u>	(phoresist\$ same solvent)	0	<u>L56</u>
<u>L55</u>	(phoresist\$ near7 solvent)	0	<u>L55</u>
<u>L54</u>	L52 and (thickness near10 "T-gate")	0	<u>L54</u>
<u>L53</u>	l52 and ("dose size" or "dose tolerance" or "dose capacity")	1	<u>L53</u>
<u>L52</u>	L51 and (resist near10 ("multi-layer" or "multi-level"))	241	<u>L52</u>
<u>L51</u>	lithography and resist	14166	<u>L51</u>
<u>L50</u>	"first photoresist" and "second phoresist"	0	<u>L50</u>
<u>L49</u>	48	1194280	<u>L49</u>
<u>L48</u>	"first photoresist" and "second phoresist"p	0	<u>L48</u>
<u>L47</u>	L46 and dose	7	<u>L47</u>
<u>L46</u>	4567132	20	<u>L46</u>
<u>L45</u>	L44	0	<u>L45</u>
<i>DB=USOC; PLUR=YES; OP=OR</i>			
<u>L44</u>	4,567,132	0	<u>L44</u>
<i>DB=USPT; PLUR=YES; OP=OR</i>			
<u>L43</u>	4560458	12	<u>L43</u>
<u>L42</u>	6342449	3	<u>L42</u>
<u>L41</u>	L40 near10 opening	1	<u>L41</u>
<u>L40</u>	"50:1" near4 "aspect ratio"	147	<u>L40</u>
<u>L39</u>	L38	12	<u>L39</u>
<u>L38</u>	4560458	12	<u>L38</u>
<u>L37</u>	6693038	1	<u>L37</u>
<u>L36</u>	6342449	3	<u>L36</u>
<u>L35</u>	634449	10	<u>L35</u>
<u>L34</u>	L32	0	<u>L34</u>
<u>L33</u>	L32	0	<u>L33</u>

DB=USOC; PLUR=YES; OP=OR

L32 6342449

0 L32

L31 L30

0 L31

DB=TDBD; PLUR=YES; OP=OR

L30 L29

0 L30

DB=DWPI; PLUR=YES; OP=OR

L29 L28

0 L29

DB=EPAB; PLUR=YES; OP=OR

L28 L27

0 L28

DB=JPAB; PLUR=YES; OP=OR

L27 (contact or via) and L24

0 L27

DB=PGPB; PLUR=YES; OP=OR

L26 L25

0 L26

DB=USPT; PLUR=YES; OP=OR

L25 (contact or via) and L24

22 L25

L24 L23 and (form\$5 near5 conduct\$4 near6 etched)

25 L24

L23 (doped or diffused) same (lateral\$3 near5 etch\$5)

405 L23

L22 "etch ratio" and plasma and 17

6 L22

L21 L9 and "etch raio"

0 L21

L20 L17 same torr

24 L20

L19 L17 torr

59732 L19

L18 L17 same "mT"

0 L18

L17 L15 near10 fluorine

139 L17

L16 L15 near10 fluorine9

0 L16

L15 (plasma)near8 pressure

17721 L15

L14 L13 same fluorine

4 L14

L13 (forming near5 plasma)near8 pressure

554 L13

L12 L11 same (opening or hole or via)

12 L12

L11 (fluorine near5 gas) near7 ((etch\$4) near 10("titanium" or "titanium-nitride" or titanium compound" or titanium alloy"))

53 L11

L10 (fluorine near5 gas) near7 ((dielectric or insulat\$5) near5 (etch\$5)) near10 temperature

4 L10

L9 (fluorine near5 gas) near7 (etch\$5) near10 temperature

67 L9

L8 L7

507 L8

L7 (fluorine near5 gas) same (etch\$5) same temperature

507 L7

L6 6451705 and (etch\$5 near4 temperature)

2 L6

L5 L1 and (etch\$5 near14 temperature)

0 L5

L4 L1 and (etch\$5 near4 temperature)

0 L4

L3 L1 and temperature

4 L3

L2 L1 and temperature

1305302 L2

L1 6720256

4 L1

END OF SEARCH HISTORY

Refine Search

Search Results -

Terms	Documents
(photolithography same ("GKRS 6202") same ("ARCH 8250"))	0

Database:

- US Pre-Grant Publication Full-Text Database
- US Patents Full-Text Database
- US OCR Full-Text Database
- EPO Abstracts Database
- JPO Abstracts Database
- Derwent World Patents Index
- IBM Technical Disclosure Bulletins

Search:

Search History

DATE: Wednesday, May 04, 2005 [Printable Copy](#) [Create Case](#)

<u>Set</u>	<u>Hit</u>	<u>Set</u>
<u>Name</u>	<u>Count</u>	<u>Name</u>
side by side		result set
DB=USPT; PLUR=YES; OP=OR		
<u>L74</u> (photolithography same ("GKRS 6202") same ("ARCH 8250"))	0	<u>L74</u>
DB=PGPB; PLUR=YES; OP=OR		
<u>L73</u> L72	0	<u>L73</u>
DB=TDBD; PLUR=YES; OP=OR		
<u>L72</u> L71	0	<u>L72</u>
DB=DWPI; PLUR=YES; OP=OR		
<u>L71</u> L70	0	<u>L71</u>
DB=JPAB; PLUR=YES; OP=OR		
<u>L70</u> L69	0	<u>L70</u>
DB=EPAB; PLUR=YES; OP=OR		
<u>L69</u> L68	0	<u>L69</u>
DB=USOC; PLUR=YES; OP=OR		
<u>L68</u> L67	0	<u>L68</u>

DB=USPT; PLUR=YES; OP=OR

<u>L67</u>	(photolithography same (GKRS 6202) same (ARCH 8250))	0	<u>L67</u>
<u>L66</u>	(lithography same (GKRS 6202) same (ARCH 8250))	0	<u>L66</u>
<u>L65</u>	(photoresist\$) same (acetal near10 polymer\$)	99	<u>L65</u>
<u>L64</u>	L63 and (acetal near10 polymer\$)	0	<u>L64</u>
<u>L63</u>	("ethyl lactate" near5 solvent) same positive same negative same photoresist\$	1	<u>L63</u>
<u>L62</u>	(("common" or "generic") near5 ("solvent" or "solvents")) near10 ("photoresists")	44	<u>L62</u>
<u>L61</u>	(("common" or "generic") near5 ("solvent" or "solvents")) near 10 ("photoresists")	66412	<u>L61</u>
<u>L60</u>	L59 near10 ("common" or "generic")	980	<u>L60</u>
<u>L59</u>	solvent\$ near 10 ("photoresists")	70524	<u>L59</u>
<u>L58</u>	photoresist near10 ("common solvent" or "generic solvent")	12	<u>L58</u>
<u>L57</u>	photoresist same ("common solvent" or "generic solvent")	52	<u>L57</u>
<u>L56</u>	(phoresist\$ same solvent)	0	<u>L56</u>
<u>L55</u>	(phoresist\$ near7 solvent)	0	<u>L55</u>
<u>L54</u>	L52 and (thickness near10 "T-gate")	0	<u>L54</u>
<u>L53</u>	152 and ("dose size" or "dose tolerance" or "dose capacity")	1	<u>L53</u>
<u>L52</u>	L51 and (resist near10 ("multi-layer" or "multi-level"))	241	<u>L52</u>
<u>L51</u>	lithography and resist	14166	<u>L51</u>
<u>L50</u>	"first photoresist" and "second phoresist"	0	<u>L50</u>
<u>L49</u>	48	1194280	<u>L49</u>
<u>L48</u>	"first photoresist" and "second phoresist"p	0	<u>L48</u>
<u>L47</u>	L46 and dose	7	<u>L47</u>
<u>L46</u>	4567132	20	<u>L46</u>
<u>L45</u>	L44	0	<u>L45</u>

DB=USOC; PLUR=YES; OP=OR

<u>L44</u>	4,567,132	0	<u>L44</u>
<i>DB=USPT; PLUR=YES; OP=OR</i>			
<u>L43</u>	4560458	12	<u>L43</u>
<u>L42</u>	6342449	3	<u>L42</u>
<u>L41</u>	L40 near10 opening	1	<u>L41</u>
<u>L40</u>	"50:1" near4 "aspect ratio"	147	<u>L40</u>
<u>L39</u>	L38	12	<u>L39</u>
<u>L38</u>	4560458	12	<u>L38</u>
<u>L37</u>	6693038	1	<u>L37</u>
<u>L36</u>	6342449	3	<u>L36</u>
<u>L35</u>	634449	10	<u>L35</u>
<u>L34</u>	L32	0	<u>L34</u>
<u>L33</u>	L32	0	<u>L33</u>

DB=USOC; PLUR=YES; OP=OR

<u>L32</u>	6342449	0	<u>L32</u>
<u>L31</u>	L30	0	<u>L31</u>
	<i>DB=TDBD; PLUR=YES; OP=OR</i>		
<u>L30</u>	L29	0	<u>L30</u>
	<i>DB=DWPI; PLUR=YES; OP=OR</i>		
<u>L29</u>	L28	0	<u>L29</u>
	<i>DB=EPAB; PLUR=YES; OP=OR</i>		
<u>L28</u>	L27	0	<u>L28</u>
	<i>DB=JPAB; PLUR=YES; OP=OR</i>		
<u>L27</u>	(contact or via) and L24	0	<u>L27</u>
	<i>DB=PGPB; PLUR=YES; OP=OR</i>		
<u>L26</u>	L25	0	<u>L26</u>
	<i>DB=USPT; PLUR=YES; OP=OR</i>		
<u>L25</u>	(contact or via) and L24	22	<u>L25</u>
<u>L24</u>	L23 and (form\$5 near5 conduct\$4 near6 etched)	25	<u>L24</u>
<u>L23</u>	(doped or diffused) same (lateral\$3 near5 etch\$5)	405	<u>L23</u>
<u>L22</u>	"etch ratio" and plasma and 17	6	<u>L22</u>
<u>L21</u>	L9 and "etch ratio"	0	<u>L21</u>
<u>L20</u>	L17 same torr	24	<u>L20</u>
<u>L19</u>	L17 torr	59732	<u>L19</u>
<u>L18</u>	L17 same "mT"	0	<u>L18</u>
<u>L17</u>	L15 near10 fluorine	139	<u>L17</u>
<u>L16</u>	L15 near10 fluorine9	0	<u>L16</u>
<u>L15</u>	(plasma)near8 pressure	17721	<u>L15</u>
<u>L14</u>	L13 same fluorine	4	<u>L14</u>
<u>L13</u>	(forming near5 plasma)near8 pressure	554	<u>L13</u>
<u>L12</u>	L11 same (opening or hole or via)	12	<u>L12</u>
<u>L11</u>	(fluorine near5 gas) near7 ((etch\$4) near 10("titanium" or "titanium-nitride" or titanium compound" or titanium alloy"))	53	<u>L11</u>
<u>L10</u>	(fluorine near5 gas) near7 ((dielectric or insulat\$5) near5 (etch\$5)) near10 temperature	4.	<u>L10</u>
<u>L9</u>	(fluorine near5 gas) near7 (etch\$5) near10 temperature	67	<u>L9</u>
<u>L8</u>	L7	507	<u>L8</u>
<u>L7</u>	(fluorine near5 gas) same (etch\$5) same temperature	507	<u>L7</u>
<u>L6</u>	6451705 and (etch\$5 near4 temperature)	2	<u>L6</u>
<u>L5</u>	L1 and (etch\$5 near14 temperature)	0	<u>L5</u>
<u>L4</u>	L1 and (etch\$5 near4 temperature)	0	<u>L4</u>
<u>L3</u>	L1 and temperature	4	<u>L3</u>
<u>L2</u>	L1and temperature	1305302	<u>L2</u>
<u>L1</u>	6720256	4	<u>L1</u>

END OF SEARCH HISTORY

Refine Search

Search Results -

Terms	Documents
6451705 and lateral	2

Database:

US Pre-Grant Publication Full-Text Database
 US Patents Full-Text Database
 US OCR Full-Text Database
 EPO Abstracts Database
 JPO Abstracts Database
 Derwent World Patents Index
 IBM Technical Disclosure Bulletins

Search:

L25

Refine Search

Recall Text

Clear

Interrupt

Search History

DATE: Tuesday, May 03, 2005 [Printable Copy](#) [Create Case](#)

Set Name Query
 side by side

Hit Count Set Name
 result set

DB=USPT; PLUR=YES; OP=OR

<u>L25</u>	6451705 and lateral	2	<u>L25</u>
<u>L24</u>	L23 and lateral	1	<u>L24</u>
<u>L23</u>	L22 and gas	2	<u>L23</u>
<u>L22</u>	6720256	4	<u>L22</u>
<u>L21</u>	L20 and plasma and (fluorine near5 gas)	7	<u>L21</u>
<u>L20</u>	L19 and (etch\$5 near7 lateral\$5)	13	<u>L20</u>
<u>L19</u>	L18 and (etch\$5 near5 opening near5 gas)	75	<u>L19</u>
<u>L18</u>	opening near5 expos\$4 near7 surface	9452	<u>L18</u>
<u>L17</u>	17	1	<u>L17</u>
<u>L16</u>	5875205 and gasket	0	<u>L16</u>
<u>L15</u>	L6 and gasket	0	<u>L15</u>
<u>L14</u>	L7 and gasket	0	<u>L14</u>
<u>L13</u>	L12 and gasket	5	<u>L13</u>
<u>L12</u>	6265246	8	<u>L12</u>

Refine Search

Search Results -

Terms	Documents
L30	0

Database:

US Pre-Grant Publication Full-Text Database
 US Patents Full-Text Database
 US OCR Full-Text Database
 EPO Abstracts Database
 JPO Abstracts Database
 Derwent World Patents Index
 IBM Technical Disclosure Bulletins

Search:

Search History

DATE: Wednesday, May 04, 2005 [Printable Copy](#) [Create Case](#)

Set
Name Query

side by
side

DB=USOC; PLUR=YES; OP=OR

L31 L30

0 L31

DB=TDBD; PLUR=YES; OP=OR

L30 L29

0 L30

DB=DWPI; PLUR=YES; OP=OR

L29 L28

0 L29

DB=EPAB; PLUR=YES; OP=OR

L28 L27

0 L28

DB=JPAB; PLUR=YES; OP=OR

L27 (contact or via) and L24

0 L27

DB=PGPB; PLUR=YES; OP=OR

L26 L25

0 L26

DB=USPT; PLUR=YES; OP=OR

L25 (contact or via) and L24

22 L25

Hit
Count Set
Name
result set

<u>L24</u>	L23 and (form\$5 near5 conduct\$4 near6 etched)	25	<u>L24</u>
<u>L23</u>	(doped or diffused) same (lateral\$3 near5 etch\$5)	405	<u>L23</u>
<u>L22</u>	"etch ratio" and plasma and 17	6	<u>L22</u>
<u>L21</u>	L9 and "etch ratio"	0	<u>L21</u>
<u>L20</u>	L17 same torr	24	<u>L20</u>
<u>L19</u>	L17 torr	59732	<u>L19</u>
<u>L18</u>	L17 same "mT"	0	<u>L18</u>
<u>L17</u>	L15 near10 fluorine	139	<u>L17</u>
<u>L16</u>	L15 near10 fluorine9	0	<u>L16</u>
<u>L15</u>	(plasma)near8 pressure	17721	<u>L15</u>
<u>L14</u>	L13 same fluorine	4	<u>L14</u>
<u>L13</u>	(forming near5 plasma)near8 pressure	554	<u>L13</u>
<u>L12</u>	L11 same (opening or hole or via)	12	<u>L12</u>
<u>L11</u>	(fluorine near5 gas) near7 ((etch\$4) near 10("titanium" or "titanium-nitride" or titanium compound" or titanium alloy"))	53	<u>L11</u>
<u>L10</u>	(fluorine near5 gas) near7 ((dielectric or insulat\$5) near5 (etch\$5)) near10 temperature	4	<u>L10</u>
<u>L9</u>	(fluorine near5 gas) near7 (etch\$5) near10 temperature	67	<u>L9</u>
<u>L8</u>	L7	507	<u>L8</u>
<u>L7</u>	(fluorine near5 gas) same (etch\$5) same temperature	507	<u>L7</u>
<u>L6</u>	6451705 and (etch\$5 near4 temperature)	2	<u>L6</u>
<u>L5</u>	L1 and (etch\$5 near14 temperature)	0	<u>L5</u>
<u>L4</u>	L1 and (etch\$5 near4 temperature)	0	<u>L4</u>
<u>L3</u>	L1 and temperature	4	<u>L3</u>
<u>L2</u>	L1 and temperature	1305302	<u>L2</u>
<u>L1</u>	6720256	4	<u>L1</u>

END OF SEARCH HISTORY